

AMENDMENTS TO THE CLAIMS:

This listing of claims will replace all prior versions and listings of claims in the application:

1-64 (Cancelled)

65. (Currently Amended) A lip makeup composition comprising at least one cosmetically acceptable organic liquid medium and at least one styrene-free film-forming block ethylenic polymer, wherein ~~the at least one block ethylenic polymer is such that, when it is present in a sufficient amount in the composition, the lip makeup composition can form a deposit that~~ has a resistive index of greater than or equal to 80%,

and further wherein the at least one styrene-free film-forming block ethylenic polymer has a polydispersity index of greater than 2 and comprises at least one first block and at least one second block, wherein the at least one first block and the at least one second block are connected together via at least one intermediate block comprising at least one constituent monomer of the at least one first block and at least one constituent monomer of the at least one second block, wherein said at least one intermediate block is a random copolymer block, and the at least one first block is chosen from:

a) a block with a Tg of greater than or equal to 40°C.

b) a block with a Tg of less than or equal to 20°C.

c) a block with a Tg from greater than 20 to less than 40°C.

and the at least one second block is chosen from a category a), b) or c) different from the at least one first block.

66. (Currently Amended) A lip makeup composition comprising at least one cosmetically acceptable organic liquid medium and at least one non-elastomeric film-forming block ethylenic polymer, wherein ~~the at least one block ethylenic polymer is such that, when it is present in a sufficient amount in the composition,~~ the lip makeup composition ~~can form a deposit that~~ has a resistive index of greater than or equal to 80%,

and further wherein the at least one non-elastomeric film-forming block ethylenic polymer has a polydispersity index of greater than 2 and comprises at least one first block and at least one second block, wherein the at least one first block and the at least one second block are connected together via at least one intermediate block comprising at least one constituent monomer of the at least one first block and at least one constituent monomer of the at least one second block, wherein said at least one intermediate block is a random copolymer block, and the at least one first block is chosen from:

a) a block with a Tg of greater than or equal to 40°C.

b) a block with a Tg of less than or equal to 20°C.

c) a block with a Tg from greater than 20 to less than 40°C.

and the at least one second block is chosen from a category a), b) or c) different from the at least one first block.

67. (Currently Amended) The lip makeup composition according to Claim 65 wherein the lip makeup composition ~~can form a deposit that~~ has a resistive index of greater than or equal to 85%.

68. (Currently Amended) The lip makeup composition according to Claim 67, wherein the lip makeup composition ~~can form a deposit that~~ has a resistive index of greater than or equal to 95%.

69. (Currently Amended) The lip makeup composition according to Claim 65 wherein the at least one block ethylenic polymer is not soluble at ~~an active material~~ content of at least 1% by weight in water or in a mixture of water and of linear or branched lower monoalcohols containing from 2 to 5 carbon atoms, without pH modification, at room temperature (25°C).

70. (Cancelled)

71. (Currently Amended) The lip makeup composition according to Claim ~~70~~ 65, wherein the at least one first block and the at least second block are such that the difference between the glass transition temperatures (T_g) of the at least one first block and the at least one second block is greater than 10°C.

72. (Previously Presented) The lip makeup composition according to Claim 71, wherein the at least one first block and the at least second block are such that the difference between the glass transition temperatures (T_g) of the at least one first block and the at least one second block is greater than 40°C.

73. (Currently Amended) The lip makeup composition according to Claim ~~70~~ 65, wherein the at least one intermediate block has a glass transition temperature that is between the glass transition temperatures of the at least one first block and the at least one second block.

74. (Currently Amended) The lip makeup composition according to Claim ~~70~~65, wherein the at least one first block and the at least one second block of the at least one block ethylenic polymer are mutually incompatible.

75. (Cancelled)

76. (Currently Amended) The lip makeup composition according to Claim ~~76~~65, wherein the at least one block ethylenic polymer has a polydispersity index ranging from 2.8 to 6.

77. (Cancelled)

78. (Currently Amended) The lip makeup composition according to Claim ~~70~~65, wherein the at least one block ethylenic polymer comprises at least one first block with a glass transition temperature (T_g) of greater than or equal to 40°C and at least one second block with a glass transition temperature of less than or equal to 20°C.

79. (Currently Amended) The lip makeup composition according to Claim 78, wherein the proportion of the at least one first block ranges from 20% to 90% by weight of the at least one block ethylenic polymer relative to the total weight of the composition.

80. (Currently Amended) The lip makeup composition according to Claim 79, wherein the proportion of the at least one first block ranges from 50% to 70% by weight of the at least one block ethylenic polymer relative to the total weight of the composition.

81. (Currently Amended) The lip makeup composition according to Claim 78, wherein the proportion of the at least one second block with a T_g of less than or equal to 20°C ranges from 5% to 75% by weight of the at least one block ethylenic polymer relative to the total weight of the composition.

82. (Currently Amended) The lip makeup composition according to Claim 81, wherein the proportion of the at least one second block with a Tg of less than or equal to 20°C ranges from 25% to 45% by weight of the at least one block ethylenic polymer relative to the total weight of the composition.

83. (Currently Amended) The lip makeup composition according to Claim 7065, wherein the at least one block polymer comprises at least one first block with a glass transition temperature (Tg) of between 20 and 40°C and at least one second block with a glass transition temperature of less than or equal to 20°C or a glass transition temperature of greater than or equal to 40°C.

84. (Currently Amended) The lip makeup composition according to Claim 83, wherein the proportion of the at least one first block with a Tg of between 20 and 40°C ranges from 10% to 85% by weight of the at least one block ethylenic polymer relative to the total weight of the composition.

85. (Currently Amended) The lip makeup composition according to Claim 84, wherein the proportion of the at least one first block with a Tg of between 20 and 40°C ranges from 50% to 70% by weight of the at least one block ethylenic polymer relative to the total weight of the composition.

86. (Previously Presented) The lip makeup composition according to Claim 83, wherein the at least one second block has a Tg of greater than or equal to 40°C.

87. (Currently Amended) The lip makeup composition according to Claim 83, wherein the proportion of the at least one second block with a Tg of greater than or equal to 40°C ranges from 10% to 85% by weight of the at least one block ethylenic polymer relative to the total weight of the composition.

88. (Currently Amended) The lip makeup composition according to Claim 87, wherein the proportion of the at least one second block with a Tg of greater than or equal to 40°C ranges from 30% to 70% by weight of the at least one film-forming block ethylenic polymer relative to the total weight of the composition.

89. (Previously Presented) The lip makeup composition according to Claim 83, wherein the at least one second block has a Tg of less than or equal to 20°C.

90. (Currently Amended) The lip makeup composition according to Claim ~~77~~65, wherein the proportion of the at least one block with a glass transition temperature of less than or equal to 20°C ranges from 20% to 90% by weight of the at least one block ethylenic polymer relative to the total weight of the composition.

91. (Currently Amended) The lip makeup composition according to Claim 90, wherein the proportion of the at least one block with a glass transition temperature of less than or equal to 20°C ranges from 50% to 70% by weight of the at least one block ethylenic polymer relative to the total weight of the composition.

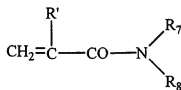
92. (Currently Amended) The lip makeup composition according to Claim ~~77~~65, wherein the at least one block with a Tg of greater than or equal to 40°C is totally or partially derived from at least one monomer whose homopolymer has a glass transition temperature of greater than or equal to 40°C.

93. (Previously Presented) The lip makeup composition according to Claim 92, wherein the at least one block with a Tg of greater than or equal to 40°C is totally or partially derived from at least one monomer whose homopolymer has a glass transition temperature ranging from 60°C to 120°C.

94. (Previously Presented) The lip makeup composition according to Claim 92, wherein the at least one block with a Tg of greater than or equal to 40°C is a copolymer derived from at least one monomer whose homopolymer has a glass transition temperature of greater than or equal to 40°C.

95. (Currently Amended) The lip makeup composition according to Claim 92, wherein the at least one monomer whose homopolymer has a glass transition temperature of greater than or equal to 40°C is chosen from the following monomers:

- methacrylates of formula $\text{CH}_2 = \text{C}(\text{CH}_3)\text{-COOR}_1$ in which R_1 is a C_1 to C_4 linear or branched unsubstituted alkyl group or R_1 is a C_4 to C_{12} cycloalkyl group,
- acrylates of formula $\text{CH}_2 = \text{CH-COOR}_2$
in which R_2 is a C_4 to C_{12} cycloalkyl group and
- (meth)acrylamides of formula:



in which R_7 and R_8 , which may be identical or different, are chosen from hydrogen atoms and C_1 to C_{12} linear or branched alkyl groups; or R_7 is hydrogen and R_8 is a 1,1-dimethyl-3-oxobutyl group, and R' is chosen from hydrogen anand methyl—~~and mixtures thereof.~~

96. (Currently Amended) The lip makeup composition according to Claim 92, wherein the at least one monomer whose homopolymer has a glass transition temperature of greater than or equal to 40°C is chosen from methyl methacrylate, isobutyl methacrylate and isobornyl (meth)acrylate, ~~and mixtures thereof.~~

97. (Currently Amended) The lip makeup composition according to Claim ~~77~~65, wherein the at least one block with a Tg of greater than or equal to 40°C is a homopolymer.

98. (Currently Amended) The lip makeup composition according to Claim ~~77~~65, wherein the at least one block with a Tg of less than or equal to 20°C is totally or partially derived from at least one monomer whose homopolymer has a glass transition temperature of less than or equal to 20°C.

99. (Previously Presented) The lip makeup composition according to Claim 98, wherein the at least one block with a Tg of less than or equal to 20°C is totally or partially derived from at least one monomer whose homopolymer has a glass transition temperature ranging from -50°C to 0°C.

100. (Currently Amended) The lip makeup composition according to Claim 98, wherein the at least one monomer whose homopolymer has a glass transition temperature of less than or equal to 20°C is chosen from the following monomers:

- acrylates of formula $\text{CH}_2 = \text{CHCOOR}_3$, wherein

R_3 is a linear or branched C_1 to C_{12} unsubstituted alkyl group, with the exception of the tert-butyl group, in which at least one hetero atom chosen from O, N and S is optionally intercalated;

- methacrylates of formula $\text{CH}_2 = \text{C}(\text{CH}_3)\text{-COOR}_4$, R_4 is a linear or branched C_6 to C_{12} unsubstituted alkyl group, in which at least one hetero atom chosen from O, N and S is optionally intercalated;

- vinyl esters of formula $\text{R}_5\text{-CO-O-CH} = \text{CH}_2$

in which R_5 is a linear or branched C_4 to C_{12} alkyl group,

- C₄ to C₁₂ alkyl vinyl ethers; and
- N-(C₄ to C₁₂) alkyl acrylamides.

101. (Previously Presented) The lip makeup composition according to Claim 98, wherein the at least one monomer whose homopolymer has a glass transition temperature of less than or equal to 20°C is chosen from alkyl acrylates whose alkyl chain contains from 1 to 10 carbon atoms, with the exception of the tert-butyl group.

102. (Currently Amended) The lip makeup composition according to Claim ~~77~~65, wherein the at least one block with a glass transition temperature of less than or equal to 20°C is a homopolymer.

103. (Currently Amended) The lip makeup composition according to Claim ~~77~~65, wherein the at least one block with a Tg from greater than of-between 20°C to and less than 40°C is totally or partially derived from at least one monomer whose homopolymer has a glass transition temperature ranging from 20°C to 40°C.

104. (Currently Amended) The lip makeup composition according to Claim ~~77~~65, wherein the at least one block with a Tg from greater than of-between 20°C to less than and 40°C is a homopolymer of a monomer chosen from n-butyl methacrylate, cyclodecyl acrylate, neopentyl acrylate and isodecylacrylamide.

105. (Currently Amended) The lip makeup composition according to Claim ~~77~~65, wherein the at least one block with a Tg ranging from greater than 20°C to less than 40°C from 20 to 40°C is a copolymer totally or partially derived from:

- at least one monomer whose homopolymer has a Tg of greater than or equal to 40°C; and

- at least one monomer whose homopolymer has a Tg of less than or equal to 20°C.

106. (Currently Amended) The lip makeup composition according to Claim 65 ~~77~~, wherein the at least one block with a Tg ranging from greater than 20°C to less than 40°C ~~from 20 to 40°C~~ is totally or partially derived from at least one monomer chosen from methyl methacrylate, isobornyl (meth) acrylate, trifluoroethyl methacrylate, butyl acrylate and 2-ethylhexyl acrylate, ~~and mixtures thereof.~~

107. (Currently Amended) The lip makeup composition according to Claim 65 ~~77~~, wherein the at least one first block and/or the at least one second block comprise(s) at least one additional monomer.

108. (Currently Amended) The lip makeup composition according to Claim 107, wherein the at least one additional monomer is chosen from hydrophilic monomers, and monomers containing ethylenic unsaturation comprising one or more silicon atoms, ~~and mixtures thereof.~~

109. (Currently Amended) The lip makeup composition according to Claim 107, wherein the at least one additional monomer is chosen from:

- ethylenically unsaturated monomers comprising at least one carboxylic or sulfonic acid function,

- methacrylates of formula $\text{CH}_2 = \text{C}(\text{CH}_3)\text{-COOR}_6$

in which R_6 is a linear or branched C_1 to C_4 alkyl group, the said alkyl group being substituted with at least one substituent chosen from hydroxyl groups and halogen atoms,

- methacrylates of formula $\text{CH}_2 = \text{C}(\text{CH}_3)\text{-COOR}_9$,

in which R₉ is a linear or branched C₆ to C₁₂ alkyl group in which at least one hetero atoms chosen from O, N and S is (are) optionally intercalated, the said alkyl group being substituted with at least one substituent chosen from hydroxyl groups and halogen atoms;

- acrylates of formula CH₂ = CHCOOR₁₀, ~~wherein~~

in which R₁₀ is a linear or branched C₁ to C₁₂ alkyl group substituted with at least one substituent chosen from hydroxyl groups and halogen atoms, or

R₁₀ is a C₁ to C₁₂ alkyl-O-POE (polyoxyethylene) with repetition of the oxyethylene unit 5 to 30 times, or

R₁₀ is a polyoxyethylenated group comprising from 5 to 30 ethylene oxide units;

and

- ethylenically unsaturated monomers comprising at least one tertiary amine function;

~~and mixtures thereof.~~

110. (Currently Amended) The lip makeup composition according to Claim 107, wherein the at least one additional monomer is chosen from acrylic acid, methacrylic acid and trifluoroethyl methacrylate, ~~and mixtures thereof.~~

111. (Currently Amended) The lip makeup composition according to Claim 107, wherein the at least one additional monomer is present in an amount ranging from 1% to 30% by weight relative to the total weight at least one block ethylenic polymer ~~of the at least one first block and/or the at least one second block.~~

112. (Currently Amended) The lip makeup composition according to Claim ~~65~~ 77, wherein the at least one first block and the at least one second block comprise at least one monomer chosen from (meth)acrylic acid esters, and optionally at least one monomer chosen from (meth)acrylic acid, and mixtures thereof.

113. (Currently Amended) The lip makeup composition according to Claim ~~65~~ 77, wherein each of the at least one first block and the at least one second block is totally derived from at least one monomer chosen from (meth)acrylic acid esters, and optionally from at least one monomer chosen from (meth)acrylic acid, and mixtures thereof.

114. (Previously Presented) The lip makeup composition according to Claim 66, wherein the at least one block polymer is styrene-free.

115. (Currently Amended) The lip makeup composition according to Claim 65, wherein the at least one block ethylenic polymer ~~block polymer~~ has a weight-average mass (Mw) of less than or equal to 300,000.

116. (Currently Amended) The lip makeup composition according to Claim 115, wherein the at least one block ethylenic polymer ~~block polymer~~ has a weight-average mass (Mw) ranging from 45,000 to 150,000.

117. (Currently Amended) The lip makeup composition according to Claim 65, wherein the at least one block ethylenic polymer ~~block polymer~~ has a number-average mass (Mn) of less than or equal to 70,000.

118. (Currently Amended) The lip makeup composition according to Claim 117, wherein the at least one block ethylenic polymer ~~block polymer~~ has a number-average mass (Mn) ranging from 12,000 to 50,000.

119. (Currently Amended) The lip makeup composition according to Claim 65, wherein the at least one block ethylenic polymer ~~block-polymer~~ is not an elastomer.

120. (Currently Amended) The lip makeup composition according to Claim 65, wherein the at least one block ethylenic polymer ~~block-polymer~~ is present in an amount ranging from 0.1% to 60% by weight relative to the total weight of the composition.

121. (Currently Amended) The lip makeup composition according to Claim 120, wherein the at least one block ethylenic polymer ~~block-polymer~~ is present in an amount ranging from 1% to 40% by weight relative to the total weight of the composition.

122. (Previously Presented) The lip makeup composition according to Claim 65, further comprising at least one volatile oil.

123. (Previously Presented) The lip makeup composition according to Claim 122, wherein the at least one volatile oil is chosen from octamethylcyclotetrasiloxane, decamethylcyclopentasiloxane, dodecamethylcyclohexasiloxane, heptamethylhexyltrisiloxane, heptamethyloctyltrisiloxane, octamethyltrisiloxane, decamethyltetrasiloxane, isododecane, isodecane and isohexadecane.

124. (Previously Presented) The lip makeup composition according to Claim 122, wherein the at least one volatile oil is present in an amount ranging from 1% to 70% by weight relative to the total weight of the composition.

125. (Previously Presented) The lip makeup composition according to Claim 124, wherein the at least one volatile oil is present in an amount ranging from 10% to 35% by weight relative to the total weight of the composition.

126. (Previously Presented) The lip makeup composition according to Claim 65, further comprising a non-volatile oil.

127. (Previously Presented) The lip makeup composition according to Claim 126, wherein the non-volatile oil is chosen from hydrocarbon-based non-volatile oils and silicone non-volatile oils.

128. (Previously Presented) The lip makeup composition according to Claim 126, wherein the non-volatile oil is present in an amount ranging from 1% to 80% by weight relative to the total weight of the composition.

129. (Previously Presented) The lip makeup composition according to Claim 128, wherein the non-volatile oil is present in an amount ranging from 20% to 50% by weight relative to the total weight of the composition.

130. (Currently Amended) The lip makeup composition according to Claim 65, further comprising at least one fatty substance that is solid at room temperature and—
chosen from waxes, pasty fatty substances and gums,~~and mixtures thereof.~~

131. (Currently Amended) The lip makeup composition according to Claim 65, wherein the lip makeup composition further comprises from 0.1% to 50% by weight of waxes relative to the total weight of the composition.

132. (Currently Amended) The lip makeup composition according to Claim 131, wherein the lip makeup composition further comprises from 1% to 30% of waxes by weight relative to the total weight of the composition.

133. (Previously Presented) The lip makeup composition according to Claim 65, further comprising at least one dyestuff.

134. (Currently Amended) The lip makeup composition according to Claim 65, further comprising at least one cosmetic ingredient chosen from additional film-forming polymers, vitamins, thickeners, trace elements, softeners, sequestering agents,

fragrances, acidifying and or basifying agents, preserving agents, sunscreens, surfactants and antioxidants, ~~and mixtures thereof.~~

135. (Previously Presented) The lip makeup composition according to Claim 65, wherein the lip makeup composition is in the form of a paste or a stick.

136. (Previously Presented) The lip makeup composition according to Claim 65, wherein the lip makeup composition is in anhydrous form.

137. (Currently Amended) A cosmetic assembly comprising:

a) at least one container delimiting at least one compartment, the at least one container being closed by a closing member; and

b) a lip makeup composition placed inside the at least one compartment, wherein the lip makeup composition comprises:

at least one cosmetically acceptable organic liquid medium, and

at least one styrene-free film-forming block ethylenic polymer,

~~wherein the at least one block ethylenic polymer is such that, when it is present in a sufficient amount in the composition, the lip makeup composition can form a deposit that has a resistive index of greater than or equal to 80%.~~

and further wherein the at least one styrene-free film-forming block ethylenic polymer has a polydispersity index of greater than 2 and comprises at least one first block and at least one second block, wherein the at least one first block and the at least one second block are connected together via at least one intermediate block comprising at least one constituent monomer of the at least one first block and at least one constituent monomer of the at least one second block, wherein said at least one

intermediate block is a random copolymer block, and the at least one first block is chosen from:

- a) a block with a Tg of greater than or equal to 40°C,
- b) a block with a Tg of less than or equal to 20°C,
- c) a block with a Tg from greater than 20 to less than 40°C,

and the at least one second block is chosen from a category a), b) or c) different from the at least one first block.

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138. (Currently Amended) A cosmetic assembly comprising:

a) at least one container delimiting at least one compartment, the at least one container being closed by a closing member; and

b) a lip makeup composition placed inside the at least one compartment,

wherein the lip makeup composition comprises:

at least one cosmetically acceptable organic liquid medium, and

at least one non-elastomeric film-forming block ethylenic polymer,

~~wherein the at least one block ethylenic polymer is such that, when it is present in a sufficient amount in the composition, the lip makeup composition can form a deposit that has a resistive index of greater than or equal to 80%.~~

and further wherein the at least one non-elastomeric film-forming block ethylenic polymer has a polydispersity index of greater than 2 and comprises at least one first block and at least one second block, wherein the at least one first block and the at least one second block are connected together via at least one intermediate block comprising at least one constituent monomer of the at least one first block and at least one

constituent monomer of the at least one second block, wherein said at least one intermediate block is a random copolymer block, and the at least one first block is chosen from:

a) a block with a Tg of greater than or equal to 40°C.

b) a block with a Tg of less than or equal to 20°C.

c) a block with a Tg from greater than 20 to less than 40°C.

and the at least one second block is chosen from a category a), b) or c).
different from the at least one first block.

139. (Previously Presented) The cosmetic assembly according to Claim 137, wherein the at least one container is at least partially formed from at least one thermoplastic material.

140. (Previously Presented) The cosmetic assembly according to Claim 137, wherein the at least one container is at least partially formed from at least one non-thermoplastic material.

141. (Previously Presented) The cosmetic assembly according to Claim 137, wherein in the closed position of the at least one container, the closing member is screwed onto the container.

142. (Currently Amended) The cosmetic assembly according to Claim 137, wherein in the closed position of the at least one container, the closing member is coupled to the at least one container by ~~in a manner other than by screwing, including~~ by click-fastening, bonding or welding.

143. (Currently Amended) A cosmetic process for making up the lips, comprising applying a lip makeup composition to the lips, wherein the lip makeup composition comprises:

at least one cosmetically acceptable organic liquid medium, and

at least one styrene-free film-forming block ethylenic polymer,

~~wherein the at least one block ethylenic polymer is such that, when it is present in a sufficient amount in the composition, the lip makeup composition can form a deposit that has a resistive index of greater than or equal to 80%.~~

and further wherein the at least one styrene-free film-forming block ethylenic polymer has a polydispersity index of greater than 2 and comprises at least one first block and at least one second block, wherein the at least one first block and the at least one second block are connected together via at least one intermediate block comprising at least one constituent monomer of the at least one first block and at least one constituent monomer of the at least one second block, wherein said at least one intermediate block is a random copolymer block, and the at least one first block is chosen from:

a) a block with a Tg of greater than or equal to 40°C,

b) a block with a Tg of less than or equal to 20°C,

c) a block with a Tg from greater than 20 to less than 40°C,

and the at least one second block is chosen from a category a), b) or c) different from the at least one first block.

144. (Currently Amended) A cosmetic process for making up the lips, comprising applying a lip makeup composition to the lips wherein the lip makeup composition comprises:

at least one cosmetically acceptable organic liquid medium, and

at least one non-elastomeric film-forming block ethylenic polymer,

~~wherein the at least one block ethylenic polymer is such that, when it is present in a sufficient amount in the composition, the lip makeup composition can form a deposit that has a resistive index of greater than or equal to 80%,~~

and further wherein the at least one non-elastomeric film-forming block ethylenic polymer has a polydispersity index of greater than 2 and comprises at least one first block and at least one second block, wherein the at least one first block and the at least one second block are connected together via at least one intermediate block comprising at least one constituent monomer of the at least one first block and at least one constituent monomer of the at least one second block, wherein said at least one intermediate block is a random copolymer block, and the at least one first block is chosen from:

a) a block with a Tg of greater than or equal to 40°C,

b) a block with a Tg of less than or equal to 20°C,

c) a block with a Tg from greater than 20 to less than 40°C,

and the at least one second block is chosen from a category a), b) or c) different from the at least one first block.

145. (Currently Amended) A method for obtaining a lip makeup composition that provides a deposit on the lips that has good resistance, said method comprising including in the lip makeup composition

at least one cosmetically acceptable organic liquid medium, and

at least one styrene-free film-forming block ethylenic polymer,

~~wherein the at least one block ethylenic polymer is such that, when it is present in a sufficient amount in the composition, the lip makeup composition can form a deposit that has a resistive index of greater than or equal to 80%,~~

and further wherein the at least one styrene-free film-forming block ethylenic polymer has a polydispersity index of greater than 2 and comprises at least one first block and at least one second block, wherein the at least one first block and the at least one second block are connected together via at least one intermediate block comprising at least one constituent monomer of the at least one first block and at least one constituent monomer of the at least one second block, wherein said at least one intermediate block is a random copolymer block, and the at least one first block is chosen from:

a) a block with a Tg of greater than or equal to 40°C,

b) a block with a Tg of less than or equal to 20°C,

c) a block with a Tg from greater than 20 to less than 40°C,

and the at least one second block is chosen from a category a), b) or c) different from the at least one first block.

146. (Currently Amended) A method for obtaining a lip makeup composition that provides a deposit on the lips that has good resistance, said method comprising including in the lip makeup composition

at least one cosmetically acceptable organic liquid medium, and

at least one non-elastomeric film-forming block ethylenic polymer,

~~wherein the at least one block ethylenic polymer is such that, when it is present in a sufficient amount in the composition, the lip makeup composition can form a deposit that has a resistive index of greater than or equal to 80%,~~

and further wherein the at least one non-elastomeric film-forming block ethylenic polymer has a polydispersity index of greater than 2 and comprises at least one first block and at least one second block, wherein the at least one first block and the at least one second block are connected together via at least one intermediate block comprising at least one constituent monomer of the at least one first block and at least one constituent monomer of the at least one second block, wherein said at least one intermediate block is a random copolymer block, and the at least one first block is chosen from:

a) a block with a Tg of greater than or equal to 40°C,

b) a block with a Tg of less than or equal to 20°C,

c) a block with a Tg from greater than 20 to less than 40°C,

and the at least one second block is chosen from a category a), b) or c) different from the at least one first block.

147. (New) The lip makeup composition according to Claim 78, wherein the at least one first block and the at least one second block are copolymers derived from monomers chosen from isobornyl (meth)acrylate, isobutyl acrylate and acrylic acid.